ALD for Industry - 3rd Workshop and Tutorial - EFDS

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Title	ALD for Industry - 3rd Workshop and Tutorial - EFDS
When	Di, 19. März 2019 - Mi, 20. März 2019

Description

ALD for Industry - 3rd Workshop and Tutorial - EFDS

A topical workshop with focus on industrialization and commercialization of ALD for current and emerging markets. Atomic Layer Deposition (ALD) is used to deposit ultraconformal thin films with sub-nm film thickness control. The method is unique in the sense that it employs sequential self-limiting surface reactions for growth in the monolayer thickness regime. Today, ALD is a key technology in leading semiconductor technology and the field of application in other leading-edge industries is increasing rapidly. According to market estimates the equipment market alone is currently at an annual revenue of US$ 1.5-1.7 billion (2017) and it is expected to double in the next 4-5 years.

In a European context ALD was invented independently twice in Europe (Russia & Finland) and since the last 15 years Germany has grown to become one of the strongest European markets for ALD in R&D, chemicals, equipment and end users.

The Event will focus on the current markets for ALD and addresses the applications in semiconductor industry, MEMS & Sensors, Battery Technology, Medical, Display, Lightning, Barriers and Photovoltaics.

Please learn more about this event by visiting following website:

https://www.efds.org/de/veranstaltungen/event/81-ald-for-industry-3rd-workshop-and-tutorial

Venue - Berlin

Location	Berlin
City	Berlin
Country	DE